

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Priority Application Serial No. 10/293,164
Priority Filing Date November 12, 2002
 Inventor J. Brett Rolfson
 Assignee..... Micron Technology, Inc.
Priority Group Art Unit..... 1756
Priority Examiner Kathleen Duda
 Attorney's Docket No. MI22-2482
 Customer No. 021567
 Title: Ion Implant Lithography Method of Processing a Semiconductor
 Substrate (as Amended)

PRELIMINARY AMENDMENT

To: Mail Stop Patent Application
 Commissioner for Patents
 P. O. Box 1450
 Alexandria, VA 22313-1450

VIA EXPRESS MAIL

From: Mark Matkin (Tel. 509-624-4276; Fax 509-838-3424)
 Wells St. John P.S.
 601 West First Avenue, Suite 1300
 Spokane, WA 99201-3828

Please enter the following amendments prior to examining the above-identified application.

AMENDMENTS

Amendments to th Titl

Please change the title to the following: --ION IMPLANT
LITHOGRAPHY METHOD OF PROCESSING A SEMICONDUCTOR
SUBSTRATE--.